

Press Release

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University of Nancy-France purchases Nanonex Advanced Nanoimprint Tool NX-2500

Princeton NJ, Apr. 14, 2008: Nanonex Corporation, the inventor and world's leading provider in nanoimprint lithography solutions with the longest history, announces the purchase of a Nanonex NX-2500 by the Henri Poincare University at the University of Nancy, Nancy, France.

The NX-2500 was purchased by Dr. Badreddine Assouar of Laboratoire de Physique des Milieux Ionisés et Applications (LPMIA), Université Henri Poincaré Nancy I, to provide support for multi-discipline research. Nanonex is proud to support the leading edge research of the University of Nancy in the effort.

“We are very excited to see further acceptance into the European market of our patented approach to nanoimprint technology. We already have a dominant position and acceptance in the North American market and are working hard to extend this to both Europe and Asia.” Dr. Stephen Chou, Chairman and Founder.

The Nanonex NX-2500 is a full wafer nanoimprinter capable of all imprint forms: thermal, photo-curable, and embossing, with sub-5nm resolution. Based on Nanonex's unique patented Air Cushion Press™ technology, the NX-2500 offers unsurpassed uniformity regardless of backside topology, wafer or mold flatness, or backside contamination. This ACP technology also eliminates lateral shifting between the mold and substrate, which significantly increases mold lifetime.

The NX-2500 also incorporates a fully flexible Smart Sample Holder that accommodates any size of substrate or mask up to the maximum capability including arbitrary shaped geometries. Very fast process cycle times are achievable due to the small thermal mass of the design.

About Nanonex Corporation

Nanonex is the inventor of “nanoimprint lithography”, the world's first nanoimprint lithography company, and the world's leading provider of nanoimprint solutions that include equipment, masks, resists and processes. Nanonex's patented and proprietary nanoimprint lithography (NIL) solutions and Air-Cushion Press™ can manufacture 3D nanostructures with sub-5 nm resolution, large-area uniformity, accurate overlay alignment, high throughput, and low cost. Nanonex NIL solutions have been adopted by a broad spectrum of industry applications, such as optical devices, data storage,

displays, light emitting diodes, semiconductor ICs, biotech, chemical synthesis, and advanced materials. Nanonex has over 100 customers and an installed base of more than 40 tools world-wide. Visit www.nanonex.com for additional information.

[About Henri Poincare University at the University of Nancy, Nancy, France.](#) (French)

[About Henri Poincare University at the University of Nancy, Nancy, France.](#) (English)